

Erratum: Effects of Plasma-enhanced Chemical Vapor Deposition (PECVD) on the Carrier Lifetime of Al₂O₃ Passivation Stack

[J. Korean Phys. Soc. **67**, 995 (2015)]

Kuk-Hyun CHO, Young Joon CHO and Hyo Sik CHANG*

Graduate School of Energy Science Technology, Chungnam National University, Daejeon 305-764, Korea

Kyung-Joong KIM

Korea Research Institute of Standards and Science, Daejeon 305-340, Korea

Hee Eun SONG

Photovoltaic Center, Korea Institute of Energy Research, Daejeon 305-343, Korea

DOI: 10.3938/jkps.67.1708

The corresponding authors of this manuscript are Hyo Sik Chang and Hee Eun Song. The information of corresponding authors of the article need to be corrected as following. E-mail: hschang@cnu.ac.kr, hsong@kier.re.kr; Fax: +82-42-821-8839.

*E-mail: hschang@cnu.ac.kr; Fax: +82-42-821-8839